LASER IRRADIATION APPARATUS AND METHOD OF TREATING SEMICONDUCTOR THIN FILM

ABSTRACT OF THE DISCLOSURE

A laser irradiation apparatus includes a laser light generation element, a splitting element for splitting laser light generated from the laser light generation element, a light interference element for causing a first beam and a second beam of the laser light split by the splitting element to interfere with each other to form a periodic light pattern, and a phase shifting element for electro-optically shifting the phase of the first beam. The laser light generation element is a pulse oscillation laser based on laser diode excitation.



